

**Indian Institute of technology Madras
Presents**

**NPTEL
NATIONAL PROGRAMME ON TECHNOLOGY ENHANCED LEARNING**

**Lecture-12
Materials Characterization**

Fundamentals of Scanning Electron Microscopy

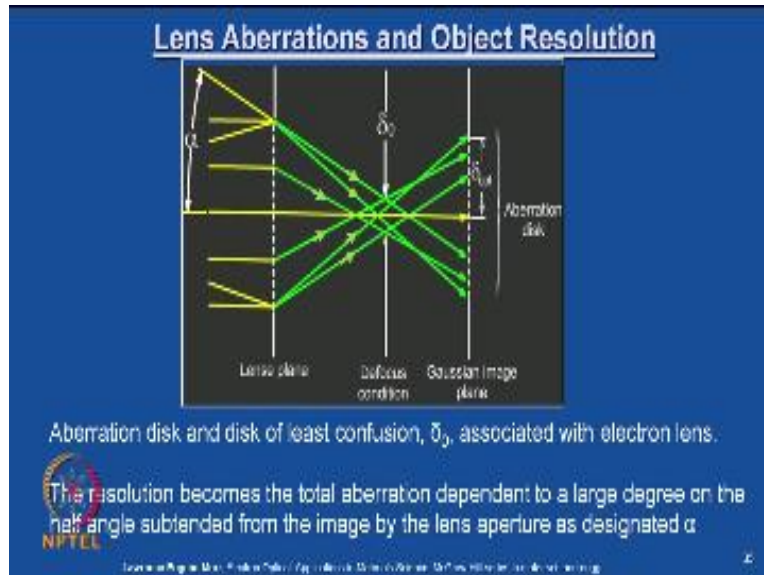
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Hello everyone welcome back to this material characterization course in the last class we just reviewed the electron optical systems and its governing principles and electron lens design and it is analogy with the light optical system and I mentioned that we will discuss the abrasions in this class and I say mentioned in the fundamentals of the optical system we have gone through all the types of operations which the glass lens will exhibit similar type of abrasions will also the electron optical system will encounter.

And then since we have already seen them in much more detailed manner but what is the each abrasion and its definition I will just mention how this is taken care in this electron optical system and then we will take up some few examples and some of the numerical significance of a spherical and chromatic aberrations, as we all know this percale operations is very important and inherent to these lenses in light optical glass lenses as well as in the electromagnetic lenses.

And we also appreciate that this is one particular abrasion which directly influence the resolution of the microscope and we will see them in little more detail so now we'll go to this.

(Refer Slide Time: 02:18)



Length separation optical resolution with regard to this electron optical system you look at this schematic what you are just seeing is a lens plane and where you have the range of α that is aperture angle and then you see that look at this ray tracing path and then each ray is focusing at different direction and basically and this is a region we say that the disk of least confusion, and then and if you look at this all this pair of rays intersecting the image plane at the different point and then eventually you see this aberration disc in the image plane.

So the point you have to remember here is it is a general schematic which is shown here and whatever the aberration we talked about whether it would be a simple astigmatism to chromatic to spherical aberration all what all these separations they do to this light ray or electron beam they have they are directing this electron beam into a different focal point whether it is on axis or half axis that we have seen.


So if you just think of all the aberrations which impair the resolution of the optical system or electromagnetic clean system it is the total combination of all these aberrations put together so you can consider this schema take a general schematic where you see this the distance δ is the defocusing condition and this is also considered as the disk of least confusion and then you see

the abrasion disk which we have already seen in the beginning and then you see that δ optimum with associated with the electron lengths in general.

So the resolution becomes the total abrasion depending dependent to a large degree on the half angle subtended from the image by the lens aperture as designated α this we have already seen so I want to emphasis again please have make sure that you understand this. So you have the it is not a completely focused condition this could be because of any aberration but this is the smallest distance that is δ naught is the least confusion and then and if you look at this δ optimum which is much larger in the image plane.

So you may see that you are at the D focusing condition your remains resolution is better is that so it may be the case we will see in the coming slide.

(Refer Slide Time: 05:53)



Lens Aberrations and Object Resolution

- The ultimate resolution of the object signal is influenced by mechanical flaws in the lens design (which produce imperfect lens field), pole-piece fabrication and also by mutual repulsion of electrons at constricted points (e.g. lens apertures etc.) along the optical axis, particularly focal points
- The variation in electron energy at various points in the beam give rise to image distortions and contribute generally to loss of contrast and sharpness
- The lens aberrations primarily responsible for deviations in electron ray intersections and concomitant loss in image clarity may be classified as geometrical aberrations, chromatic aberrations and field-effect aberrations including a space charge of the electrons

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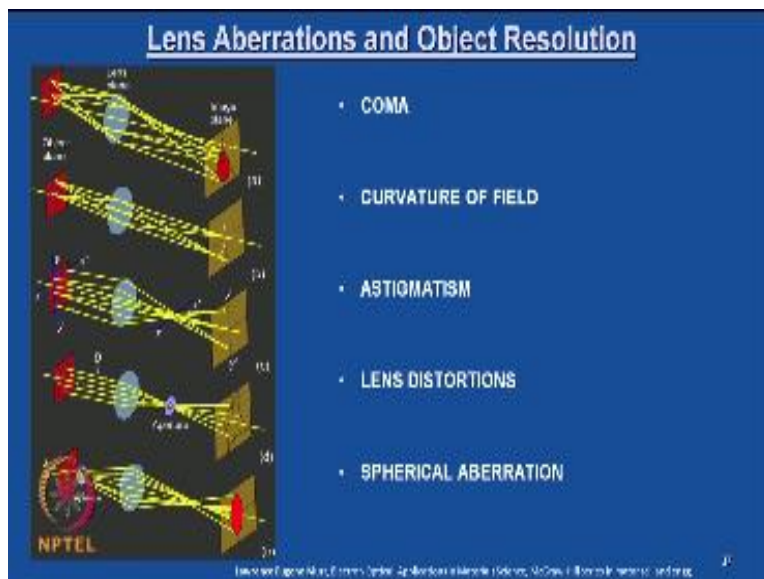
So let me read out some few introductory remarks for this abrasions of the electron optical or electromagnetic line systems the ultimate resolution of the object signal is influenced by mechanical flaws in the lens design which produce imperfect lens field pole piece fabrication and also by mutual repulsion of electrons are constricted points that is a focal points lens aperture etc

along the optical axis particularly the focal points the variation in electron energy at various points in the beam give rise to image distortion and contribute generally to loss of contrast and sharpness.

So this is the fundamental point which you have to keep in mind whatever happens in the electro-magnetic length system it is the variation in the electron energy at various points in a beam you raise to image distortion and causes the loss of contrast and sharpness the lengths operations primarily responsible for deviations in electron ray intersections and concomitant loss image clarity may be classified as geometrical aberrations chromatic aberrations and field effect aberrations including epic space charge of the electrons.

We will see one by one and the space charge of electrons will be we did not discuss in the light optical system we will see in this system how it is affecting the resolution.

(Refer Slide Time: 07:51)



So it is just a recap of what we have seen the type of aberrations the this the schematic I have just put it everything in one image because we have already seen them in much more detailed when we discussed in the light optical systems so the first schematic shows the coma effect and second

schematic describes the curvature of field and thirds schematic see this astigmatism and the fourth one is lens distortion and the fifth one is spherical aberration I will not describe them in detail because you have already seen it if you have a doubt you can go back to that lecture and then look at all this individual defects and then make yourself clear about this.

And it is the same thing I will only discuss about how these defects are taken care in this electron optical system.

(Refer Slide Time: 09:07)

Lens Aberrations and Object Resolution

Coma: It can be eliminated almost entirely in an electromagnetic lens by the establishment of field conditions giving rise to unity magnification

Curvature field: It is reduced by properly shaping the electromagnetic lens field

Astigmatism: The aberration is correctable by inserting stigmators in the appropriate lens systems to compensate for the non-circularity of the image beam profile on the image plane. The stigmator, containing symmetrical arrangements of tiny ferromagnets or suitable permanently magnetized components, acts to circularise the image

Lens distortions: The correction of coma in an electromagnetic lens concurrently eliminates the lens distortions as well

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In terms of coma it can be eliminated almost entirely in electromagnetic lengths by the establishment of field conditions giving rise to unity magnification and in terms of curvature field it is reduced by properly shaping the electromagnetic length speed the astigmatism on the other hand is correctable by inserting astigmatism in the appropriate length system to compensate the non circularity of the image beam profile on the image plane.

So what is stick matter the astigmatism containing symmetrical arrangements of tiny Pharaoh magnets are suitable permanently magnetized components acts to circularize the image and the lens distortion the correction of coma in an electromagnetic lens and currently eliminates the lens

distortions as well, so what you should appreciate here is in electro optical systems the most of your operations is controlled by the field strength on the field distribution in an optical system we just all the separations were compensated with the an additional glass lens here since all theory focal length everything is controlled by the field strength and your abrasions also controlled by the appropriate field strength and it is distribution in the appropriate length system.

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Lens Aberrations and Object Resolution

Coma: It can be eliminated almost entirely in an electromagnetic lens by the establishment of field conditions giving rise to unity magnification

Curvature field: It is reduced by properly shaping the electromagnetic lens field

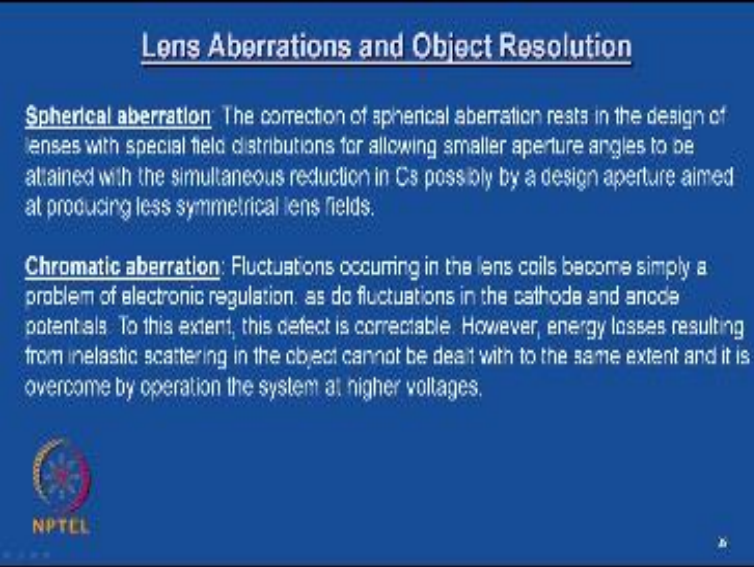
Astigmatism: The aberration is correctable by inserting stigmators in the appropriate lens systems to compensate for the non-circularity of the image beam profile on the image plane. The stigmator, containing symmetrical arrangements of tiny ferromagnets or suitable permanently magnetized components, acts to circularise the image

Lens distortions: The correction of coma in an electromagnetic lens concurrently eliminates the lens distortions as well

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So we will see the other operations.


(Refer Slide Time: 11:02)



Lens Aberrations and Object Resolution

Spherical aberration The correction of spherical aberration rests in the design of lenses with special field distributions for allowing smaller aperture angles to be attained with the simultaneous reduction in Cs possibly by a design aperture aimed at producing less symmetrical lens fields.

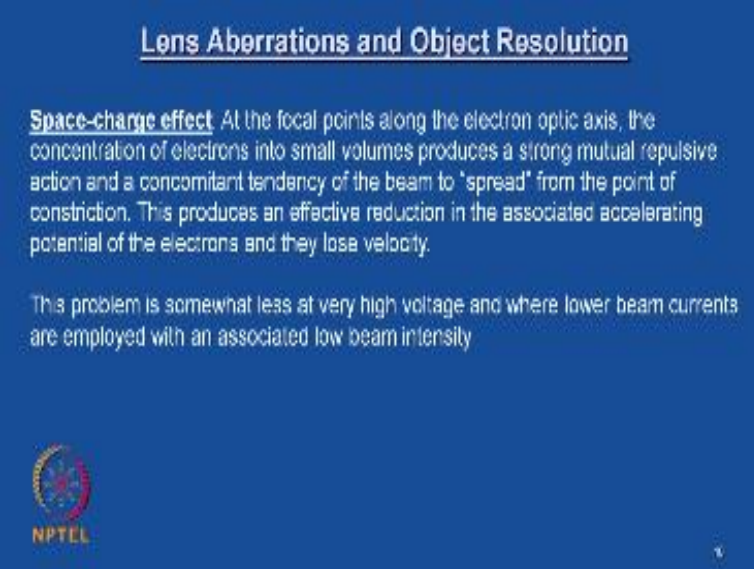
Chromatic aberration Fluctuations occurring in the lens coils become simply a problem of electronic regulation, as do fluctuations in the cathode and anode potentials. To this extent, this defect is correctable. However, energy losses resulting from inelastic scattering in the object cannot be dealt with to the same extent and it is overcome by operation the system at higher voltages.

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Spherical aberration the correction of the spherical aberration rest in the design of lens lenses with special field distributions for allowing smaller aperture angles to be attained with the simultaneous detection in CS possibly by a design aperture aimed at producing less symmetrical lens field. So as I mentioned this particular abrasion is very important and how much we can reduce this will finally determine the resolution of the optical system, and then we will see them and its numerical significance in a few minutes.

And chromatic aberration which is caused by the fluctuations occurring in the lens coils becomes simply a problem of electro electronic regulation as do fluctuations in the cathode and anode potentials to this extent this defect is correctable however the energy losses resulting from the inelastic scattering in the object cannot be dealt with to the same extent and it is overcome by operation the system at higher voltages.


(Refer Slide Time: 12:38)



Lens Aberrations and Object Resolution

Space-charge effect: At the focal points along the electron optic axis, the concentration of electrons into small volumes produces a strong mutual repulsive action and a concomitant tendency of the beam to "spread" from the point of constriction. This produces an effective reduction in the associated accelerating potential of the electrons and they lose velocity.

This problem is somewhat less at very high voltage and where lower beam currents are employed with an associated low beam intensity

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The another important aspect of this electron optical system is a space charge effect what is this space charge effect are the focal points along the electron optic axis the concentration of electrons into small volumes produces a strong mutual repulsive action and their current competent tendency of the beam to spread from the point of constriction that is from the point of focus this produces an effective reduction in the Associated accelerating potential of the electrons and they lose velocity and this problem is somewhat less at very high voltage and where lower beam currents are employed with an Associated low beam intensity.

So this particular effect is specially belonged to this electron optical system and you have to remember the aberrations which we talked about and its effect on resolution we simply assume that are we simply do not consider the specimen condition for example whatever the aberration we talked about we assume that the specimen is pure and it does not have any contaminating I mean constituents in it or it does not react with the beam and then produce its world new product that will impair the resolution.

So all this the treatment which we are talking about are the compensating effect we talked about assuming that the specimen is in the ideal condition okay so in the mathematical treatment which

you are going to look at is also in the similar manner that we are not taking the specimen effect that means we assume that specimen is ideally prepared and it does not have any contamination or any other reacting constituents with the electron beam, so now we will just take up this to spherical I mean two operations first we talked about spherical aberrations.

(Refer Slide Time: 15:14)



So what I am trying to write here is the image-forming length or the Critical beam forming lengths in an electron microscope or microprobe system in the objective lens we always talk about objective lens whether it could be a any image forming lengths or it could be an electron forming then I mean you know electron microscope political beam forming lens or it could be electron microprobe analyzer we always concerned about the operations of objective lens.

We can describe the disk of confusion caused by the spherical aberration ask that is $\delta_{s\ SP}$ δ_0 is general notation for desktop finished confusion here $\delta_{s\ SP}$ is it is exclusively caused by the spherical aberration can be represented as $2 \times CS \alpha^3$ where CS the spherical aberration coefficient which is also given by γ not SI s equal to γ naught times V naught divided by n a whole square bracket square.

So this expression you are familiar with already this is potential this is number of coil this is current which is which is which is observed to be proportional to the square of the focal length, so this can be written as C equal to γ not focal length of the two lengths and it fuck in still / ma goes well where γ is a constant ranging from hundred for strong lengths and 151 VP γ is a constant ranging from 100 for a strong length 12 p / v lines. So similarly we will see this chromatic aberration.

(Refer Slide Time: 22:14)



So as we discussed earlier it depends on electron energy R and links current fluctuation δI and this Express δ chromatic disc of confusion created by chromatic aberration can be related to 2 times format $CC \propto \delta C$ are equal to two times pc that is chromatic aberration coefficient α times δV by V naught whole square plus δI by I four square to power of three square root of the whole expression.

We write where CC o metric aberration proficient which is also given by CC equals γ not plain open link up objective where yah mon on train is a constant reading from 152 onestrongall week Glenn section first the, so you have this chromatic aberration constant is equal to gamma naught

primetimes focal length of objective and gamma naught prime is the constant varying from 0.5 to one for a strong or a weak link action respectively.

(Refer Slide Time: 26:43)



So now what we will do is we will see that how all this operations we will now try to write some expressions for objects resolution and then image quality involving all this operations which we talked about, so we see that so what I have written is as a consequence of the uncertainty principle the exact image displacement of electrons deflected from the object area will be subjected to uncertainty of discrete line displacement in the object of the order δX which is equal to L .

So this list of paste conclusion line to line extend the written as λ divided by $2 \sin \alpha$ were familiar with this expression and it can be assume like this so I read out again because of the uncertainty principle the electrons deflected from the object area will be subject to uncertainty of discrete line displacements in the object. So if α is 0.01 to 0.001radian then we can write δl is 0.5λ divided by α for example you can write in a typical electron microscope α is point zero three at hundred kv your δl could be ugly about Caroline.

This will give you an idea a typical case that you see that to δ is how to appreciate this, so now we will include the length aberrations and see how this expression is modified where so what I have done is where the length separation included in the real economical system the ultimate resolution is given by considering in addition to the light action and fertility chromatic and fir collaborations the combination of the error disk radiation that is δ optimum in the image playlist found from δ optimum = $\sqrt{\delta L L^2 + \delta (S T / 2)^2 + \delta \text{romantic} / 2^2}$.

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We consider limit of two points we always talk about point resolution as well as line the solution you can consider these two if you consider two points in the image plane the optimum your life I am the resolution limit east on point those r TP thirties point to point this cough and future this also you are familiar with already finger where again include 32 thing. So if you include this the spiracle and chromatic aberration expression into this the point-to-point discuss this transition then you obtain δ optimum point equal to $\sqrt{\delta P P S^2 + \delta (s c / 2)^2}$.

So these basic expressions are further modified by several researchers and then we can write one more general expression for the stuff least confusion I mean we will talk about all this much more detail out this is really going to affect the practical resolution when we look at the actual

microscopic operation but you should appreciate that the importance of this two spherical and chromatic aberrations of it feeling influence the resolution limit of the system.

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So what before we just look at this expression if you recall this the ray diagram which I showed in the beginning of this class where you see that the δ not was defined as discussed least Confucian in a deep focus strain and then if you look at the image plane where δ optimal read on the image plane which is much larger than the $V_0 \delta$ optimum was much larger than in the array discreet described which is larger than the D_0 .

So that came implies that if you reduce the field strength then you will automatically get the better resolution, so to emphasis this point these you get an expression for δ_0 itself that is what we have trying to show here the minimum constriction of the beam described as the discoveries from conclusion on the defocus play on the optical axis the diameter of the disco feast conclusion is given by $D_0 = \sqrt{4 \text{ times } \delta P T^2 + C S \alpha^3 / 2^2 + C \alpha \delta v / V_0^2}$.

Where $\delta P P$ is equal to point 6 1times λ / α and where $C S$ and $C C$ are the spherical and chromatic aberration proficient respectively δB is voltage change for a acceleration potential V_0 in α is an

objective aperture under. So in this class I hope you have at least have some basic idea about how this aberrations in an electron optical system is considered and its influence on the resolution of the image and leap microscope. So now we will now go on to the actual electron optical system especially we will start with a scanning electron microscopy and its working principle and its application from the next class. Thank you.

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